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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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First Named Inventor	Hiromitsu SAKAI		
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Examiner Name	Shouxiang HU		
Attorney Docket Number	Q78084		

U.S. PATENTS						
Examiner Initials* Cite No Patent Number Kind Code¹ Issue Date Name of Patentee or Applicant of cited Document		Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear				
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	3.	1 160 882	EP	A2	2001-12-05	NGK INSULATORS, LTD.		

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	4.	T. TAKEUCHI, ET AL: "Improvement of far-field pattern in nitride laser diodes", APPLIED PHYSICS LETTERS, AIP, AMERICAN INSTITUTE OF PHYSICS, MELVILLE, NY, US LNKD- DOI:10.1063/1.125201, vol. 75, no. 19, 8 November 1999 (1999-11-08), pages 2960-2962, XP012023940 ISSN: 0003-6951 * page 2960, column 2, line 8 - page 2961, column 1, line 8; figures 1, 2, 4 * * page 2962, column 1, lines 3-9 *			
	5.	C. ADELMANN, ET AL: "Atomic-layer epitaxy of GaN quantum wells and quantum dots on (0001) AIN", JOURNAL OF APPLIED PHYSICS, AMERICAN INSTITUTE OF PHYSICS. NEW YORK, US LNKD-DOI:10.1063/1.1458049, vol. 91, no. 8, 15 April 2002 (2002-04-15), pages 5498-5500, XP012056297 ISSN: 0021-8979 * page 5498, column 2, lines 7-9 * * page 5499, column 1, lines 14-28; figure 1b * * page 5499, column 2, line 26 - page 5500, column 1, line 9; figures 3a,b * * page 5500, column 2, lines 6-8, 13, 14 *			
	6.	M. MIYAMURA, ET AL: "Stranski-Krastanow growth of GaN quantum dots by metalorganic chemical vapor deposition", JOURNAL OF CRYSTAL GROWTH, ELSEVIER, AMSTERDAM, NL LNKD-DOI:10.1016/S0022-0248(01)02058-9, vol. 237-239, 1 April 2002 (2002-04-01), pages 1316-1319, XP004355989 ISSN: 0022-0248 * page 1317, column 1, lines 7-13 * * page 1317, column 1, line 20 - column 2, line 25; figures 2b, 2c, 3 * * page 1318, column 1, line 11 - page 1319, column 1, line 11; figure 4 *			
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EXAMINER SIGNATURE					
Examiner Signature	/Shouxiang Hu/	Date Considered	10/12/2010		

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through a citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ See Kind Codes of USPTO Patent Documents at www.USPTO.GOV or MPEP 901.04. 2 Enter office that issued the document, by the two-letter code (WIPO Standard ST.3). 3 For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. 4 Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. 5 Applicant is to place a check mark here if English language translation is attached.

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /S.H./